

In re Appln. of Toru YOSHIE
Application No. Unassigned

ABSTRACT AMENDMENTS

Replace the Abstract with:

An insulating film is formed on a semiconductor base material, the insulating film being predominantly composed of organic siloxane and containing an organic component which has no chemical bond to the organic siloxane. ~~Plasma~~ A plasma treatment is applied to the insulating film to remove the organic component and form a modifying layer on a surface of the insulating film.